

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Sadao KANBE et al.

Group Art Unit: 1792

Application No.: 10/796,056

Examiner: W. FLETCHER

Filed: March 10, 2004

Docket No.: 105024.02

For: SUBSTRATE FOR FORMING SPECIFIC PATTERN, AND METHOD FOR
MANUFACTURING SAME

APPLICANTS' INTERVIEW SUMMARY

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Applicants appreciate the courtesies shown to Applicants' representative by Examiner Fletcher in the August 20, 2008 interview. Applicants' separate record of the substance of the interview is incorporated into the following remarks.

During the interview, Applicants' representative explained that the 35 U.S.C. §112, second paragraph rejection and the 35 U.S.C. §102(e) rejection based on claims 3-5 should be overcome for the reasons described in the Amendment filed on July 23, 2008 (Amendment).

With regards to the 35 U.S.C. §112, second paragraph rejection, Applicants argued that claim 4, as recited in the Amendment, should overcome the present rejection. Examiner Fletcher agreed that the amendments to claim 4 overcame this rejection. As a result, he indicated that claim 4 is presently allowable.

Regarding the 35 U.S.C. §102(e) rejection, Applicants argued that Fukushima does not describe the step of forming a thin film pattern on the pattern formation region by

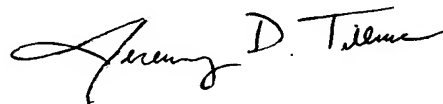
applying a fluid to the pattern formation region that exhibits a non-affinity to the sulfur compound film and an affinity to the base as described in claim 3. Furthermore, Applicants argued that Fukushima also does not describe forming a thin film pattern on the pattern formation region by applying the fluid to the pattern formation region that exhibits an affinity to the sulfur compound film and a non-affinity to the base as recited in new claim 19.

Examiner Fletcher also agreed that the Fukushima does not describe the above limitations of forming a thin film pattern, but stated that he would need to conduct an additional search before allowing the claims.

Favorable reconsideration and prompt allowance of claims 3, 4 and 19 are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



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JAO:JDT/hs

Date: August 27, 2008

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